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# INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: KOSHELEV et al.

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of

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Examiner: NOT ASSIGNED

Group Art Unit:

## U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
<i>W</i>	AR	4,494,043	01/1985	Stallings et al.			
<i>W</i>	BR	4,644,576	02/1987	Kuyel			
<i>W</i>	CR	6,414,438	07/2002	Borisov et al.			
	DR						
	ER						
	FR						
	GR						
	HR						
	IR						
	JR						
	KR						
	LR						
	MR						
	NR						

## FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclose	No
<i>W</i>	OR	0 480 617 A2	10/1991	Europe	Jewell et al.				
	PR								
	QR								
	RR								
	SR								
	TR								
	UR								

## OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

<i>W</i>	VR	Patent Abstracts of Japan, Publication No. 62176038, August 1, 1987.							
<i>W</i>	WR	Bergmann, K., et al., "Highly Repetitive, Extreme-Ultraviolet Radiation Source Based on a Gas-Discharge Plasma," <i>Applied Optics</i> , Vol. 38, No. 25, September 1, 1999, pp. 5413-17.							
<i>W</i>	XR	Va'vra, J., et al., "Soft X-Ray Production in Spark Discharges in Hydrogen, Nitrogen, Air, Argon and Xenon Gases," <i>Nuclear Instruments &amp; Methods in Physics Research, Section A</i> , Vol. 418, No. 2-3, December 1998, pp. 405-419.							
<i>W</i>	YR	Melnichuk et al., "Plasma Focus Light Source with Improved Pulse Power System," Pub. No: US 2003/0006383 A1, published January 9, 2003							

Examiner

*ZIA R. HASHMI*

Date Considered:

*3/1/04*

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.